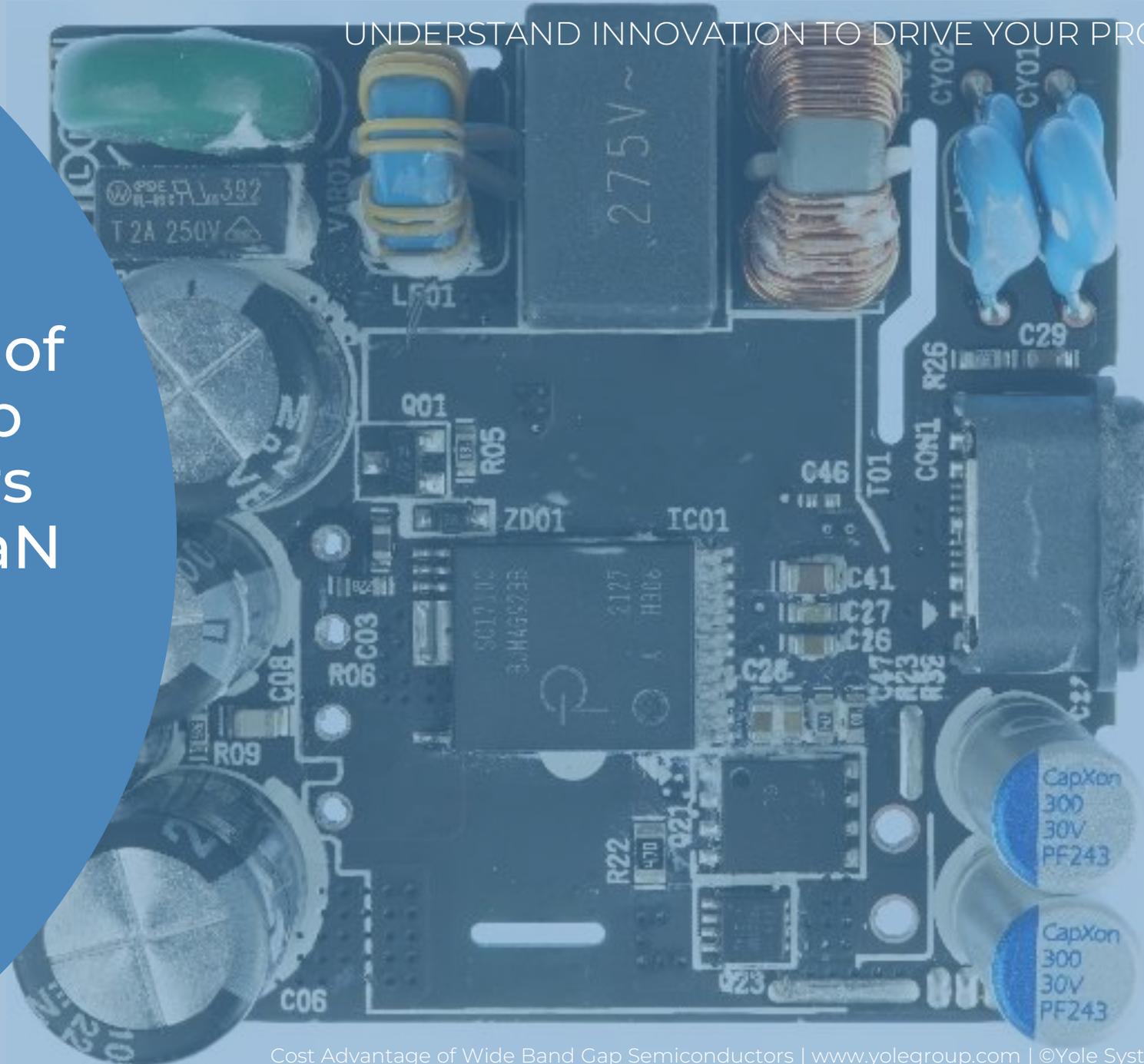
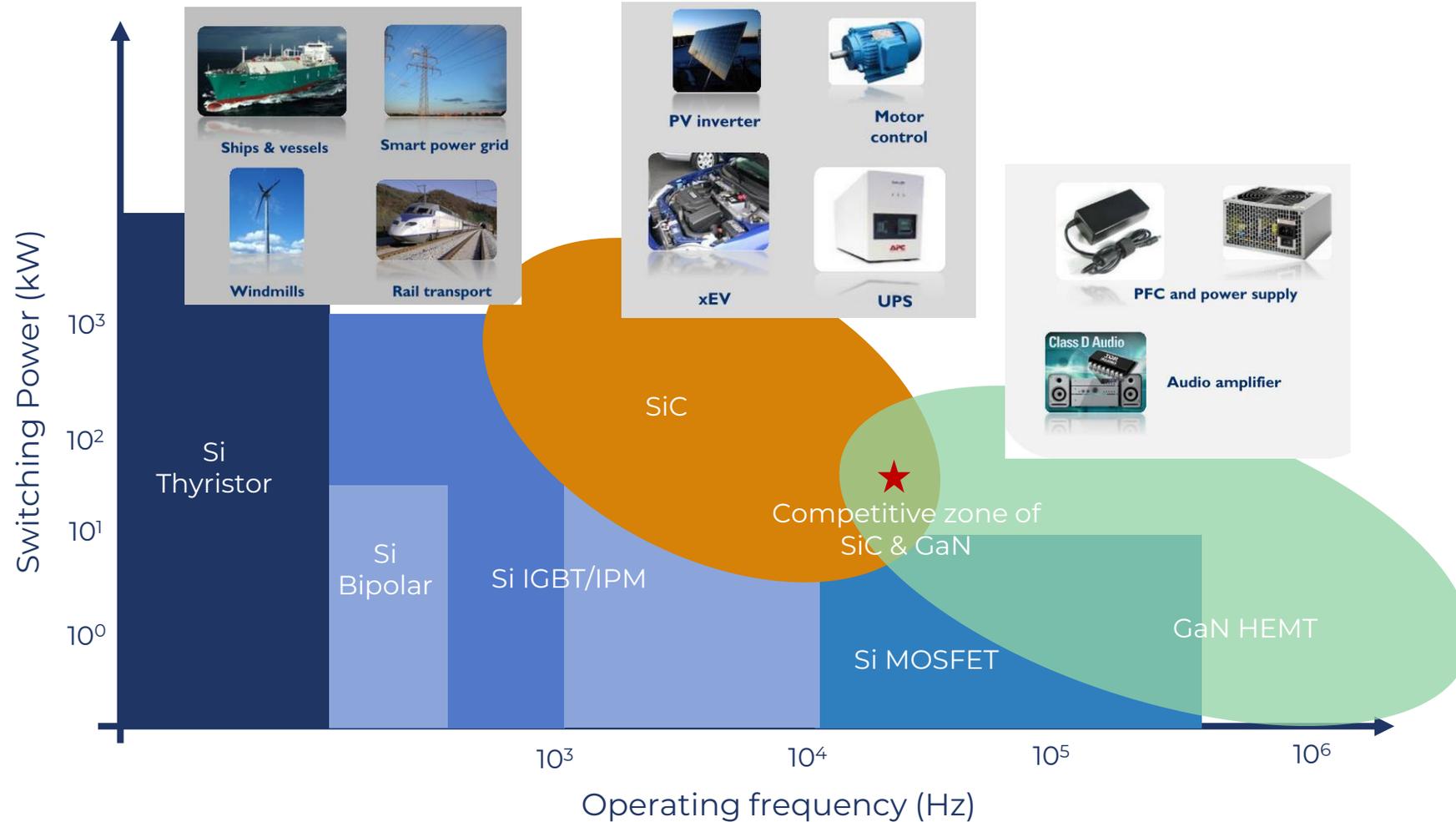


Cost Advantage of Wide Band Gap Semiconductors with focus on GaN

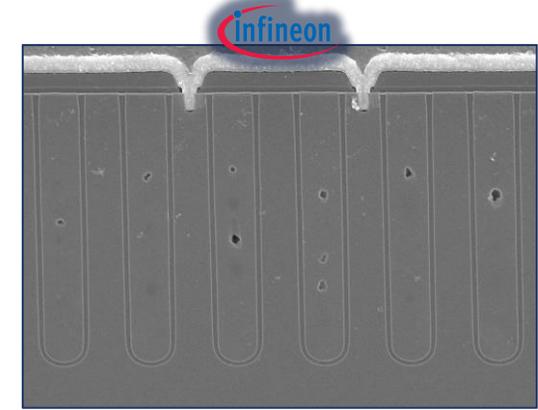
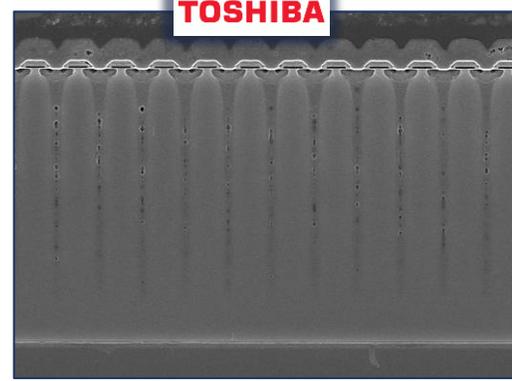
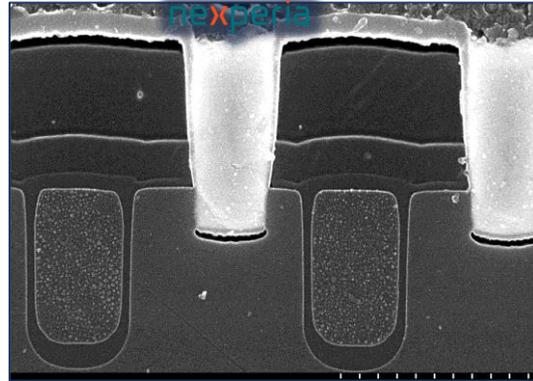


- Power Conversion Solutions
- Si Power Semiconductor Designs and Limitations
- Technical Comparison - Si vs SiC vs GaN
- GaN Device Solutions
- Cost Considerations for Discrete Power Device
 - Wafer Cost Considerations
 - System Level Cost Considerations
- Recommendations for further cost savings

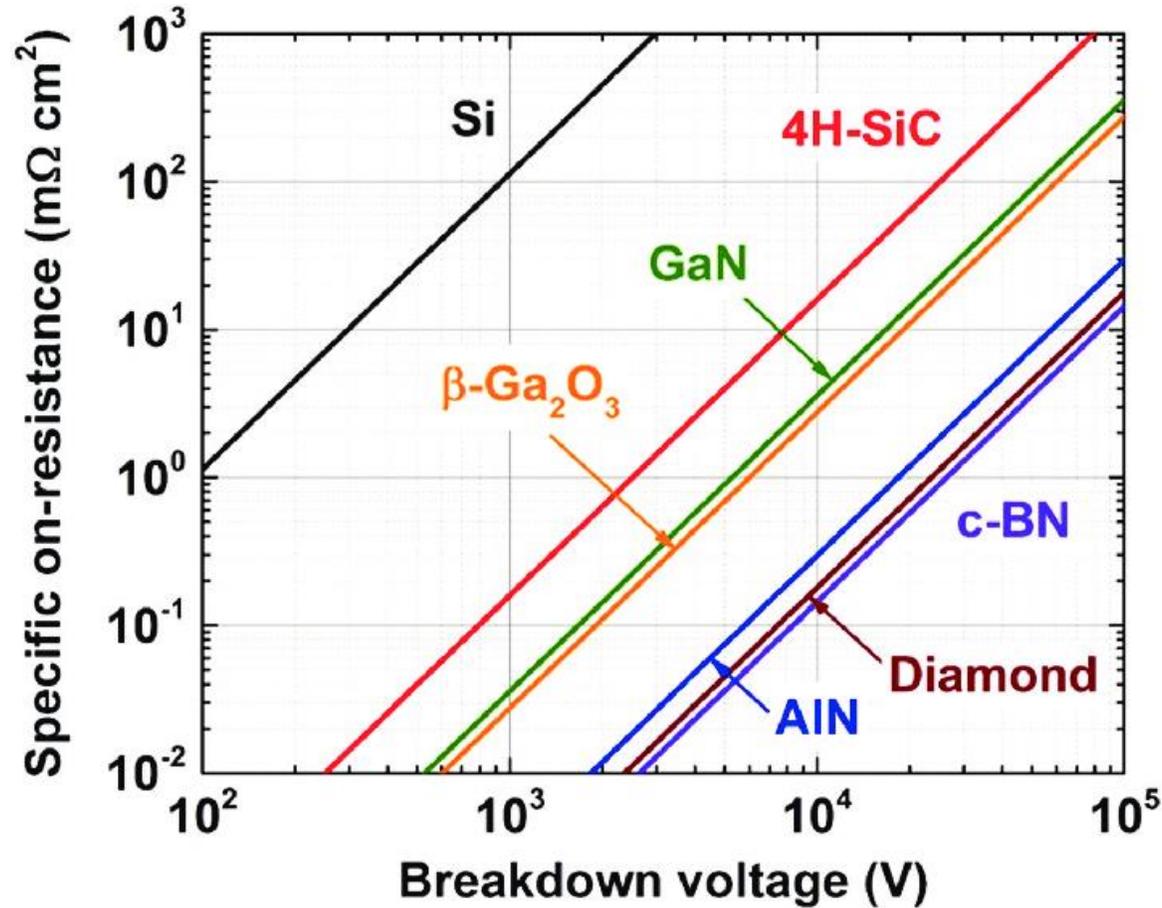
- Power electronics applications is still dominated by Si technologies, but we are seeing SiC and GaN competing for applications mainly in the medium and high voltage applications.



POWER TRANSISTOR DESIGNS AND LIMITATIONS



	Si Power MOSFET	Superjunction MOSFET	IGBT
Voltage Range	12 V - 600 V	600 V to 1000 V	400 V up to 3kV
Device type	Unipolar	Unipolar	Bipolar
On resistance	High	Low	Lowest
Cost	✓	✓✓✓	✓✓
Main Applications	Class D Audio amplifier, PFC power supply, consumer appliances	Hybrid/Electric Vehicle, Industrial Controller, PV Inverters, UPS, Hybrid/Electric Vehicle	Industrial Controller, PV Inverter, HV traction, Wind Turbines
Main Players			

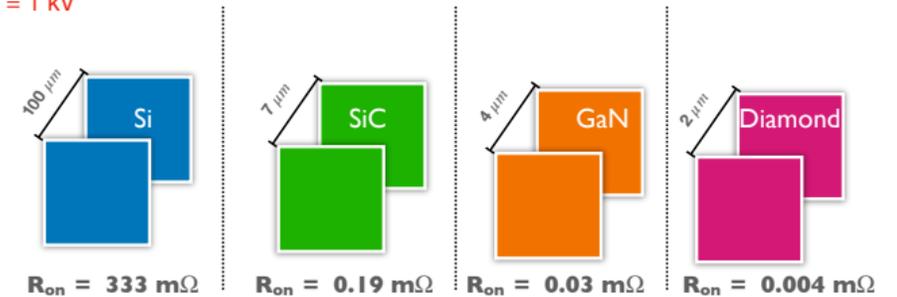


Source: J.Y Tsao, Ultrawide-Bandgap Semiconductors: Research and Opportunities

Theoretical limits define by materials properties

Property	Symbol	Si	4H-SiC	GaN	$\beta - Ga_2O_3$	Diamond
Bandgap	E_g (eV)	1.1	3.23	3.45	4.5	5.45
Sat. Drift Velocity	v_s [10^7 cm/s]	1.0	2.0	2.2	-	1.1
Electron mobility	μ_n [$cm^2/V.s$]	1500	1000	1250	300	1000
Hole mobility	μ_p [$cm^2/V.s$]	480	100	200	-	2000
Breakdown field	E_m [MV/cm]	0.3	3	2	8	10
Dielectric constant	ϵ_r	11.8	9.8	9	10	5.5
Thermal Conductivity	λ	1.5	5	1.5	0.11	22
BFM(absolute)	(MW/cm^2)	42	20000	8000	140000	970000
BFM(relative)	[Si=1]	1	550	190	3200	23000

BV = 1 kV



Manufacturing challenges vs Cost vs Reliability vs integration

Single switch



Multiple switches

Multiple functions

Multiple switches and functions

Single switch' includes only one GaN device in the package. It is the simplest solution on component level, but it implies more effort at the system level. Moreover, more discrete devices needed in a system.

More than one GaN HEMT is integrated in a chip, for example two HEMTs for a half-bridge configuration. It provides a more compact design and higher efficiency to the system.

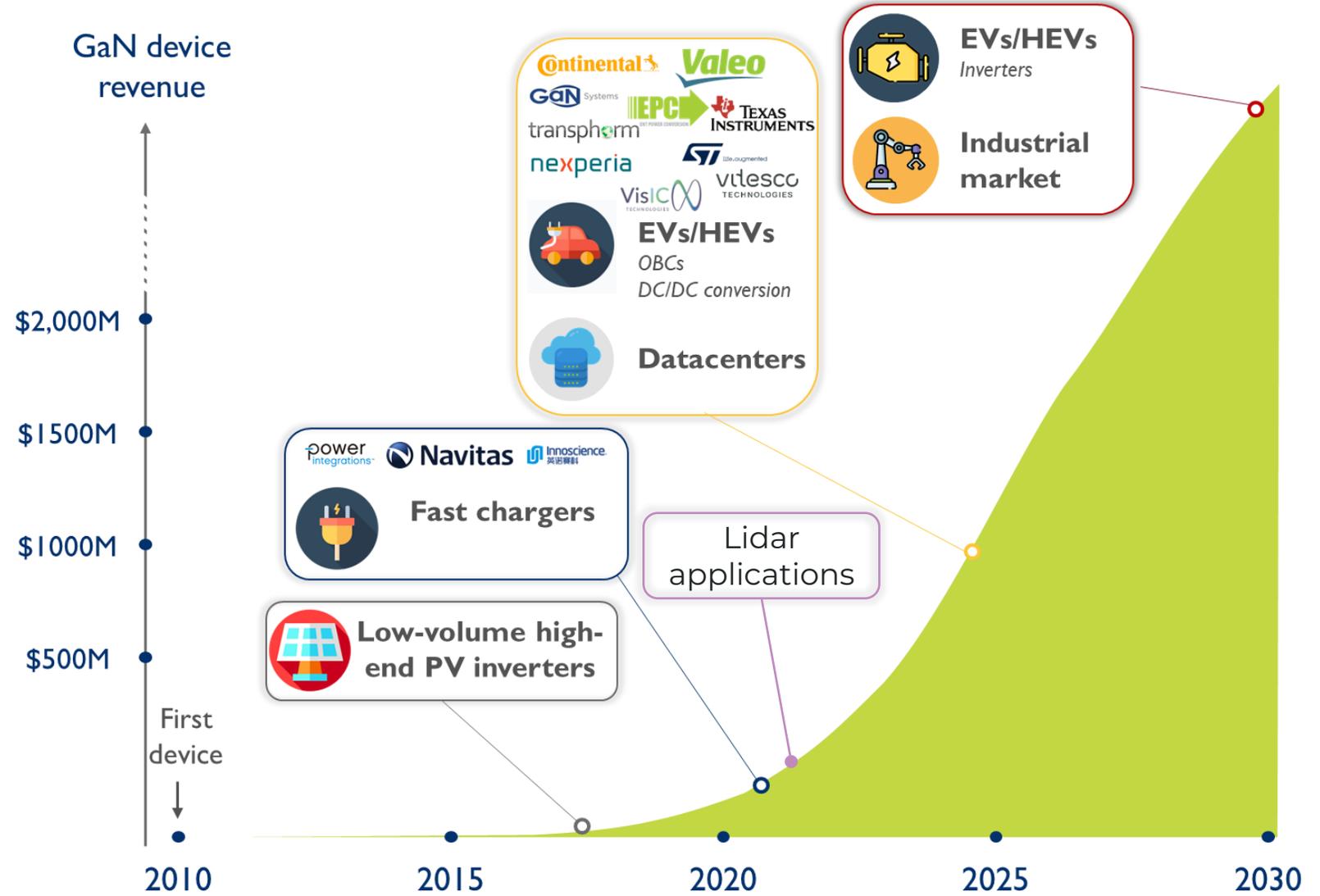
Integration of a GaN HEMT and the driver in one chip for high efficiency and good high-frequency operation. Some manufacturers using D-mode GaN integrate the driver as well.

Currently the implementation of multiple switches and functions is done by integrating multiple chips in a single package. To monolithically integrate switches there is a need for strict control of isolation to avoid any current flow or latch-ups.

GAN POWER DEVICES MARKET

Long term evolution

- Consumer fast-charger applications will continue to drive the GaN market in the short term.
- Volume shipments will ramp up in datacenters and EVs/HEVs in the mid- to long term.



Source: GaN Power 2022, Yole Intelligence

FAST CHARGERS: GaN VS. Silicon

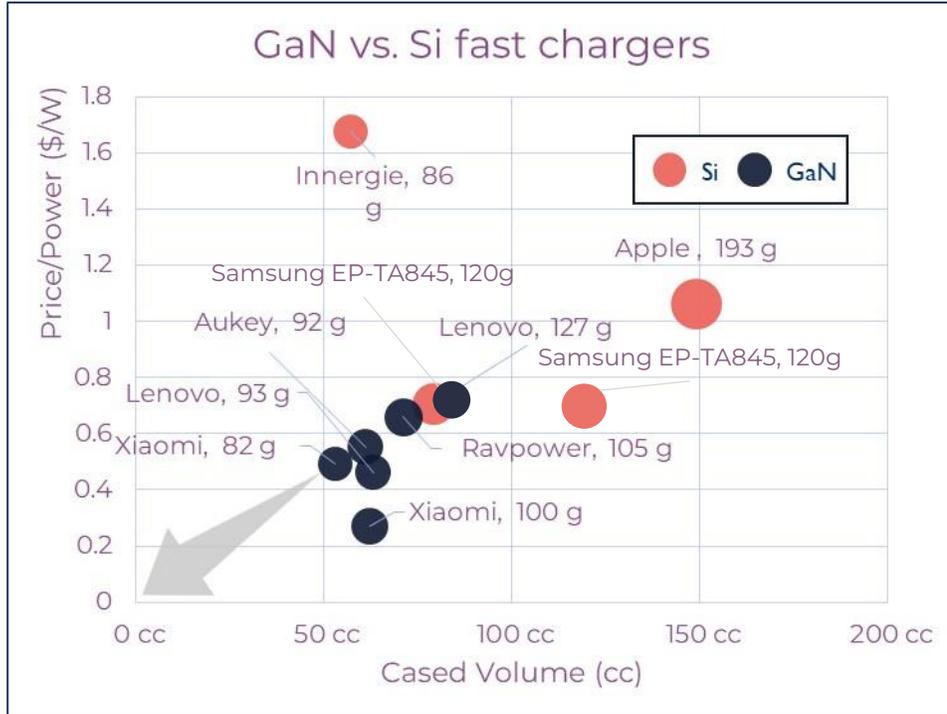
Faster, more power, smaller, lighter and lower cost

The trend is towards smartphones with a bigger screen and larger battery capacity. Fast charging is becoming a must-have technology. GaN offers numerous benefits over silicon MOSFETs such as a small form factor, high efficiency and high performance.

According to industry feedback, GaN enables an interesting cost/performance ratio compared to silicon MOSFETs beyond 45W.

On the other hand, advances in silicon MOSFETs' performance are still ongoing, with enhanced topologies like active clamp fly-back (ACF). In fact, Xiaomi have silicon MOSFET fast-chargers that can reach 120W.

Another important criteria is thermal management. In the system as a whole, the GaN solution is likely to have lower losses.



Samsung's 45W fast charger based on silicon
52x53x30 mm
Power density: 0.55 W/cm³

EP-TA845



Samsung's 45W fast charger based on GaN
48x44x28 mm
Power density: 0.76W/cm³

EP-T4510



Xiaomi's 120W fast charger based on silicon
64x61x28 mm
Power density: 1.1 W/cm³

MDY-12-ED



Xiaomi's 120W fast charger based on GaN
56x56x28 mm
Power density: 1.37 W/cm³

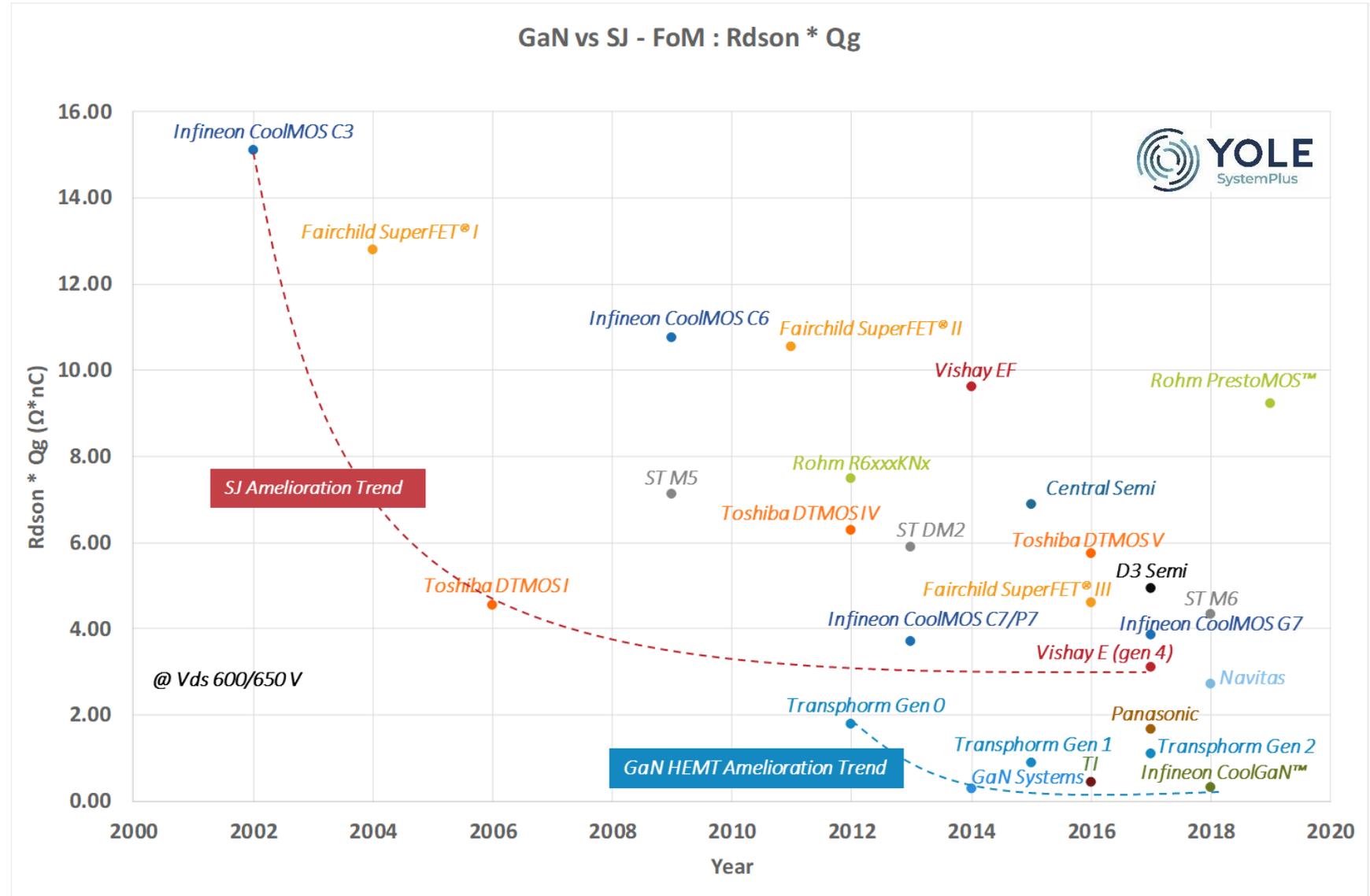
MDY-13-ET



- The bubble size represents the weight in grams of the cased charger. **All devices have output powers between 55-65W.**

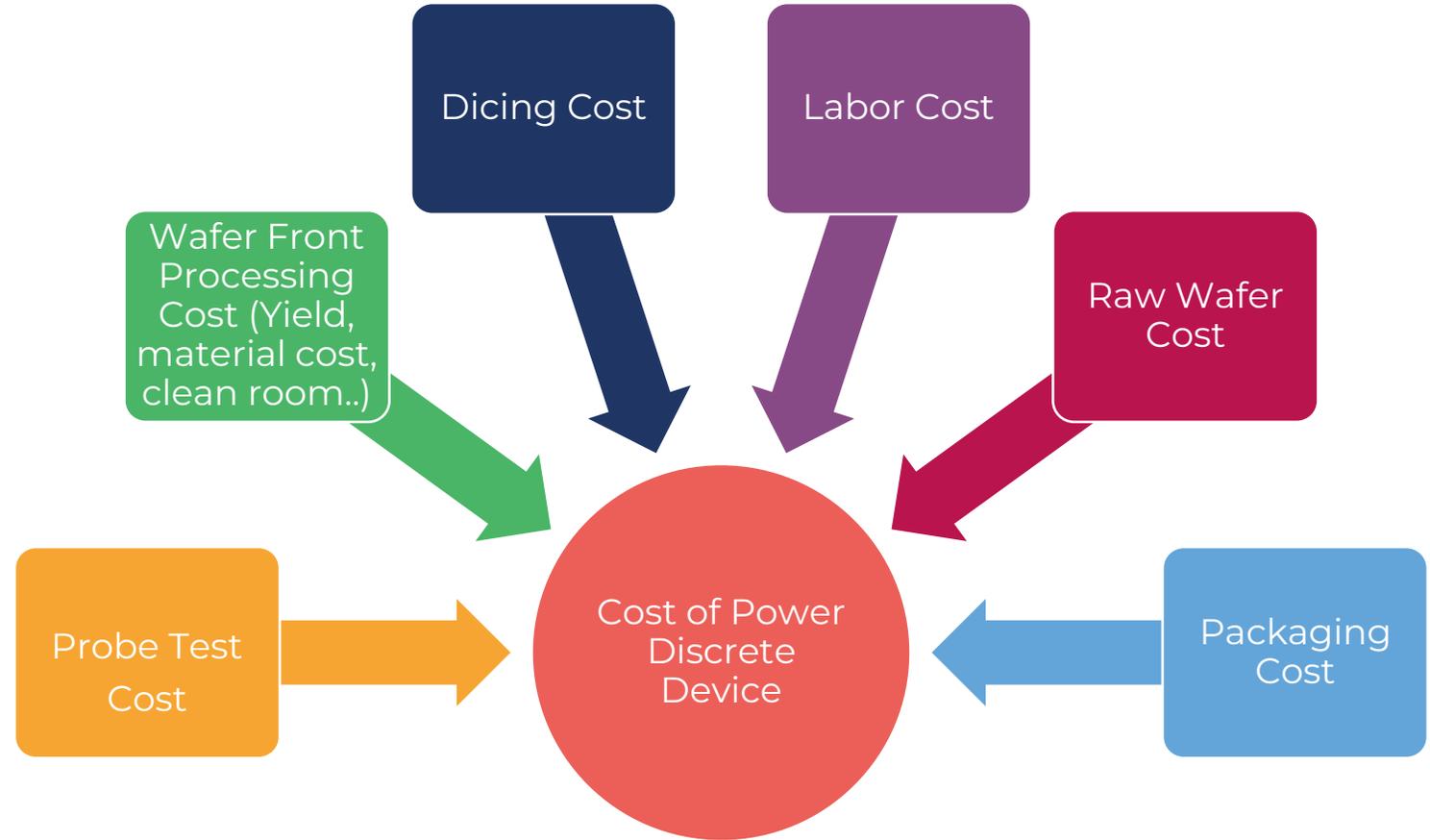
TECHNICAL COMPARISON GAN VS SI SUPERJUCTION

- Though relatively new technology, the FoM of GaN devices (650 V) are already competing with silicon superjunction devices and surpassing their performances.
- We expect to see a strong competition and continue replacement of SJ applications with GaN devices in the 600/650 V application range.



COST CONSIDERATIONS FOR DISCRETE POWER DEVICE

- ✓ Single chip vs Multi-chip solutions
- ✓ Die size (small vs large)
- ✓ Labor Cost – Supply chain
- ✓ Raw wafer (150 mm vs 200 mm vs 300 mm)
- ✓ Material Cost/Consumable Costs
- ✓ Package Assembly Cost

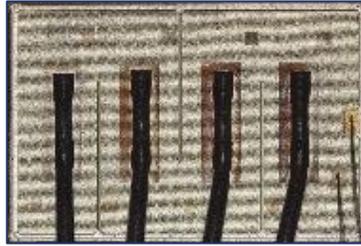
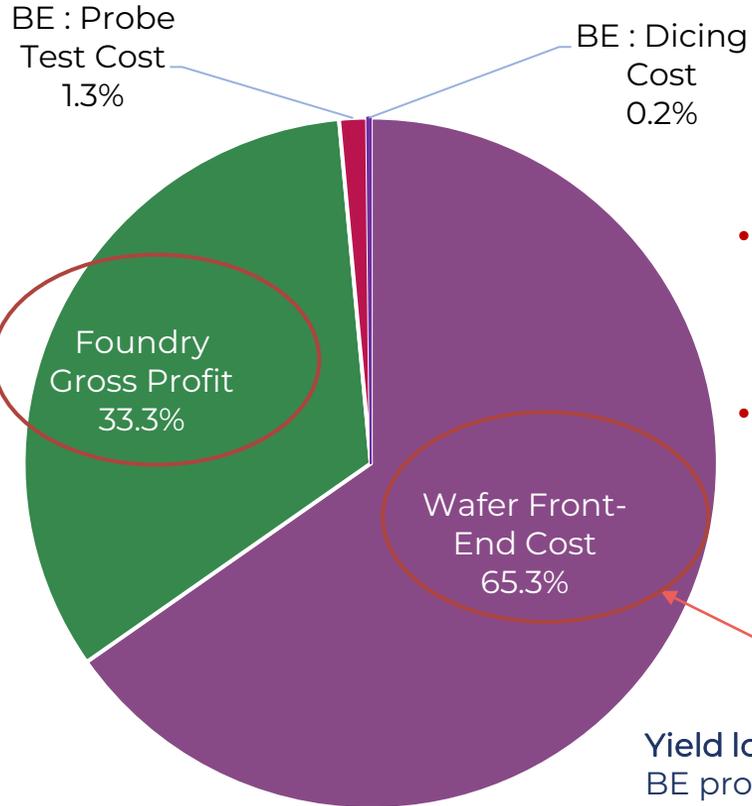
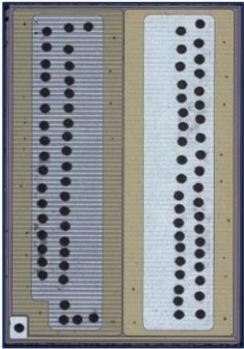


At Yole SystemPlus, we have tools to model and estimates all related manufacturing cost to near market price.

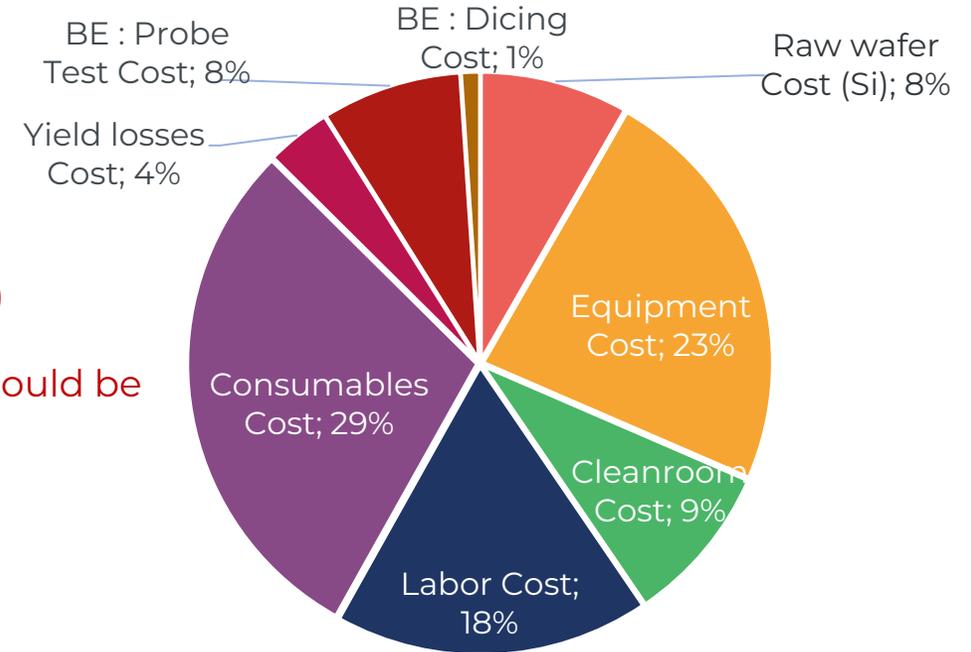
COST COMPARISON GAN VS SI SUPERJUNCTION – WAFER LEVEL

650 V Si Superjunction vs GaN

Total Wafer Cost Breakdown for GaN
650 V HEMT devices



Average Total Wafer Cost Breakdown
for 650V Superjunction MOSFET

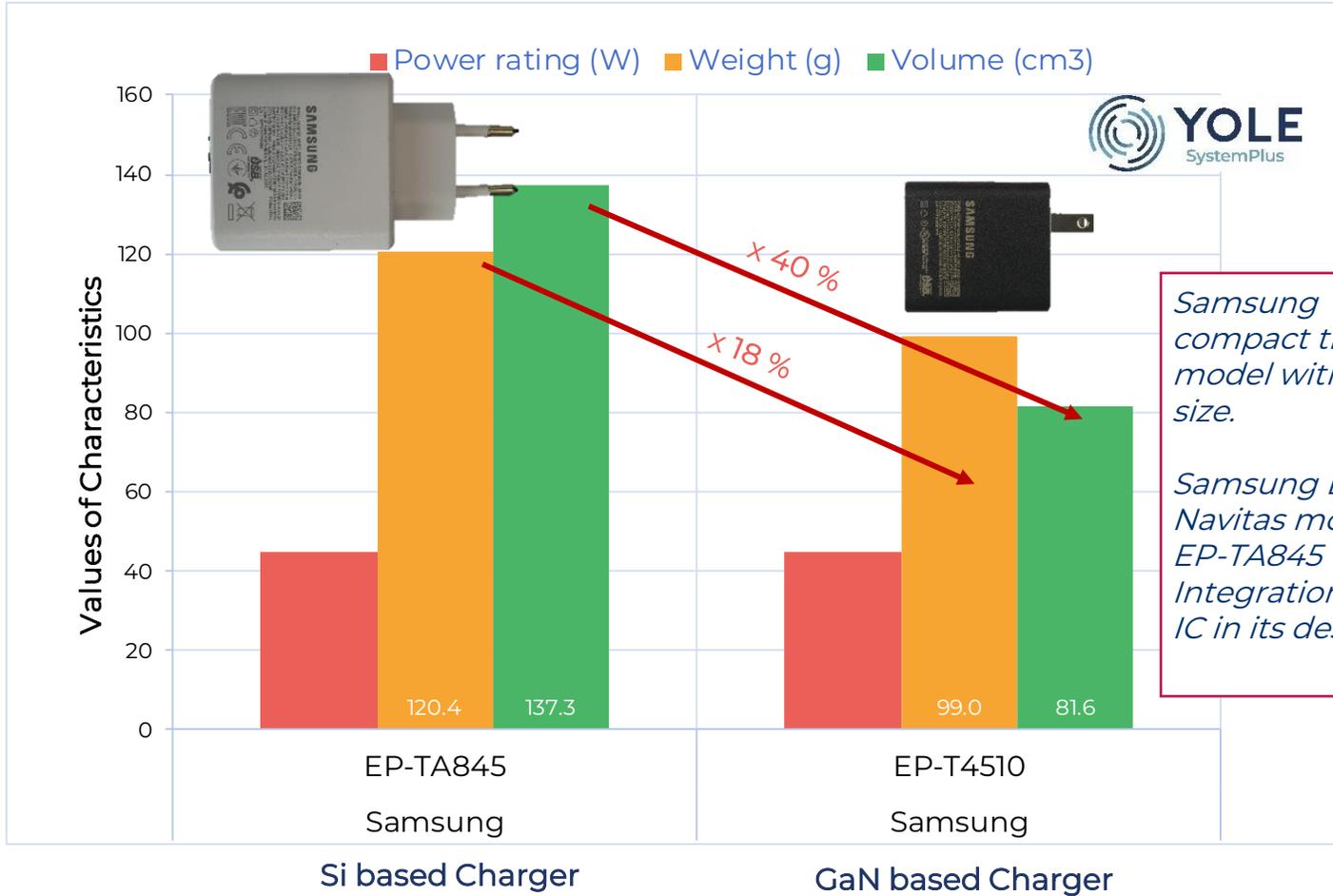


- Manufacturing Yield Improvements. (Si > 95%, GaN < 85 %)
- Vertical Integration could be considered.

Yield loss Cost, Epitaxy Cost, FE & BE process, Raw Wafer

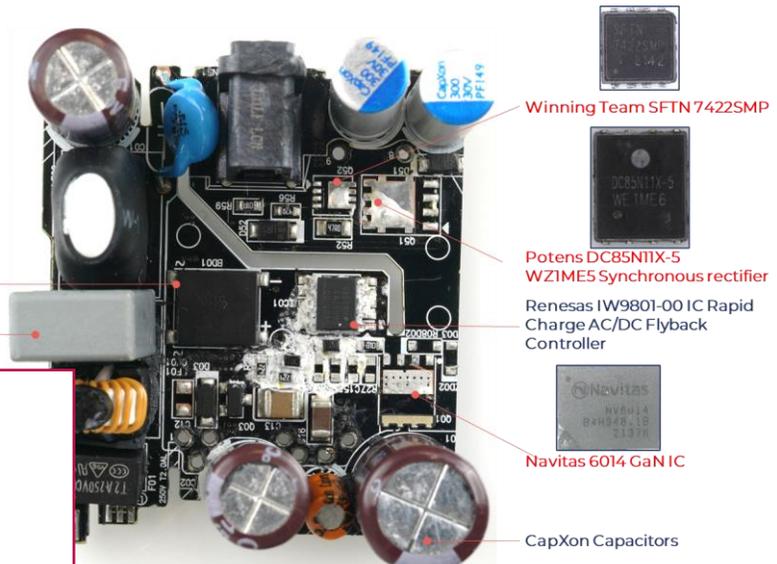
SAMSUNG POWER ADAPTERS – BOM COMPARISON

Samsung 45W Power Adapters (GaN vs Si solution)

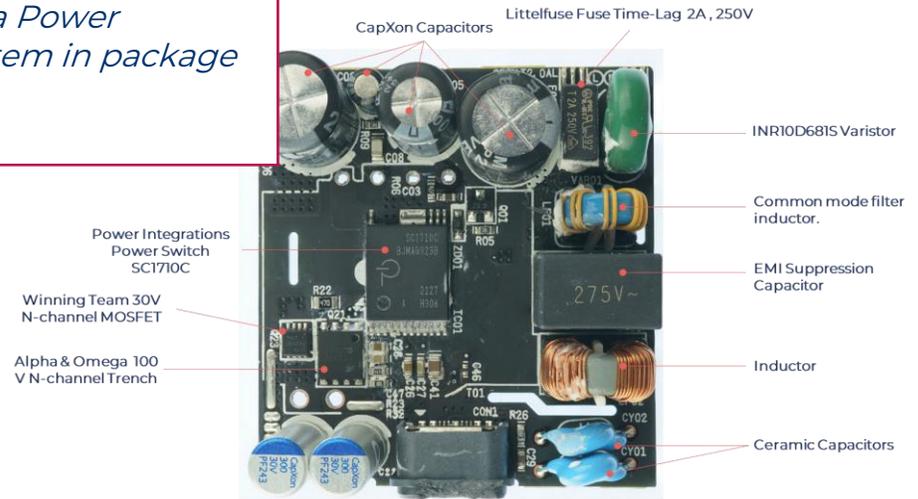


Samsung EP-T4510 is more compact than the EP-TA845 model with about 40% in the size.

Samsung EP-T4510 uses a Navitas monolithic IC while the EP-TA845 uses a Power Integrations system in package IC in its design.



Samsung EP-T4510 Top Side - Optical View ©Yole SystemPlus 2023



Samsung EP-TA845 Top Side - Optical View ©Yole SystemPlus 2023

COST COMPARISON GAN VS SI CHARGER – SYSTEM LEVEL

Samsung 45W charger EP-T4510 vs EP-TA845 model

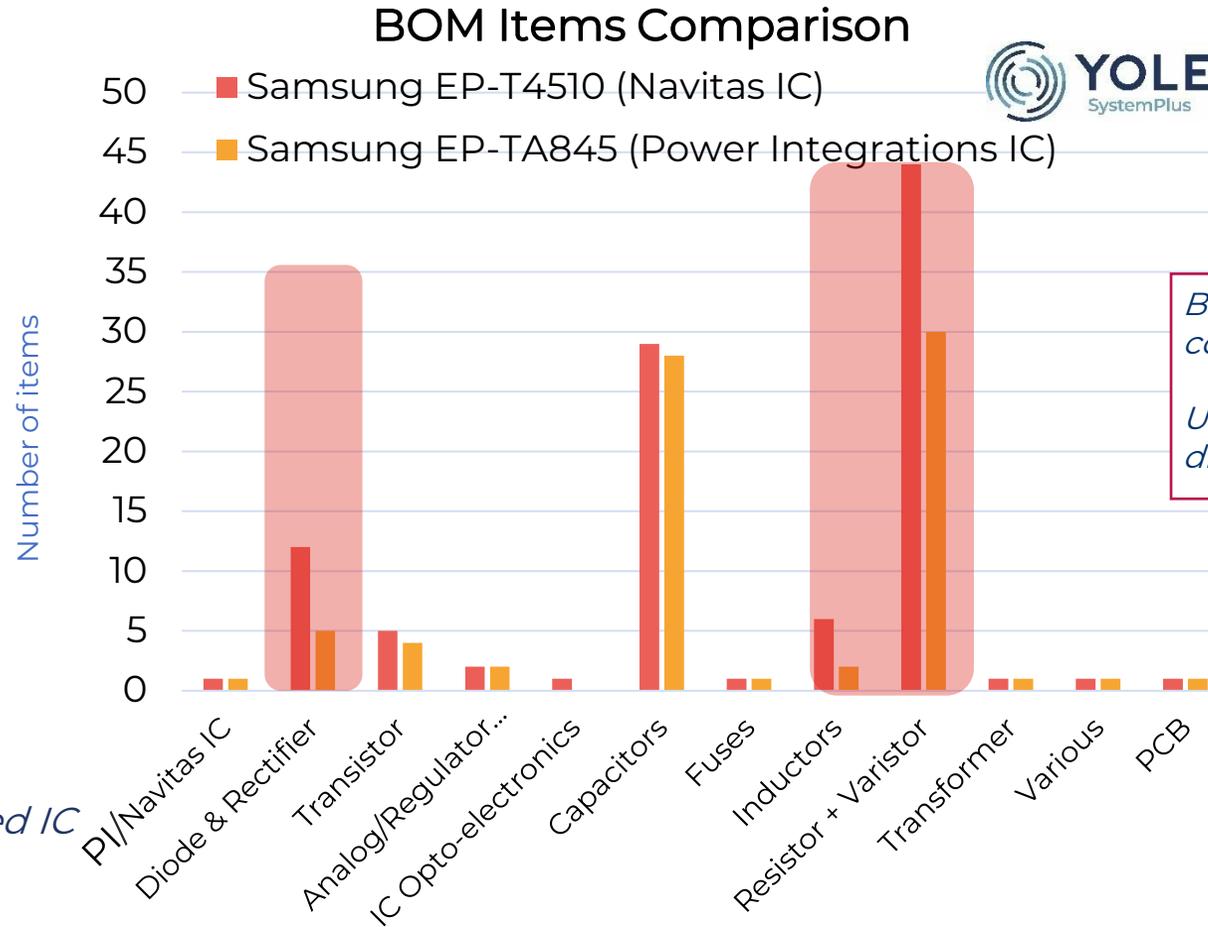
- For 45W, the Samsung charger EP-T4510 model uses more resistors, inductors and rectifiers elements than the EP-TA845 model.



Navitas GaN IC



Power Integrations Si based IC



BOM Items is a design choice consideration.

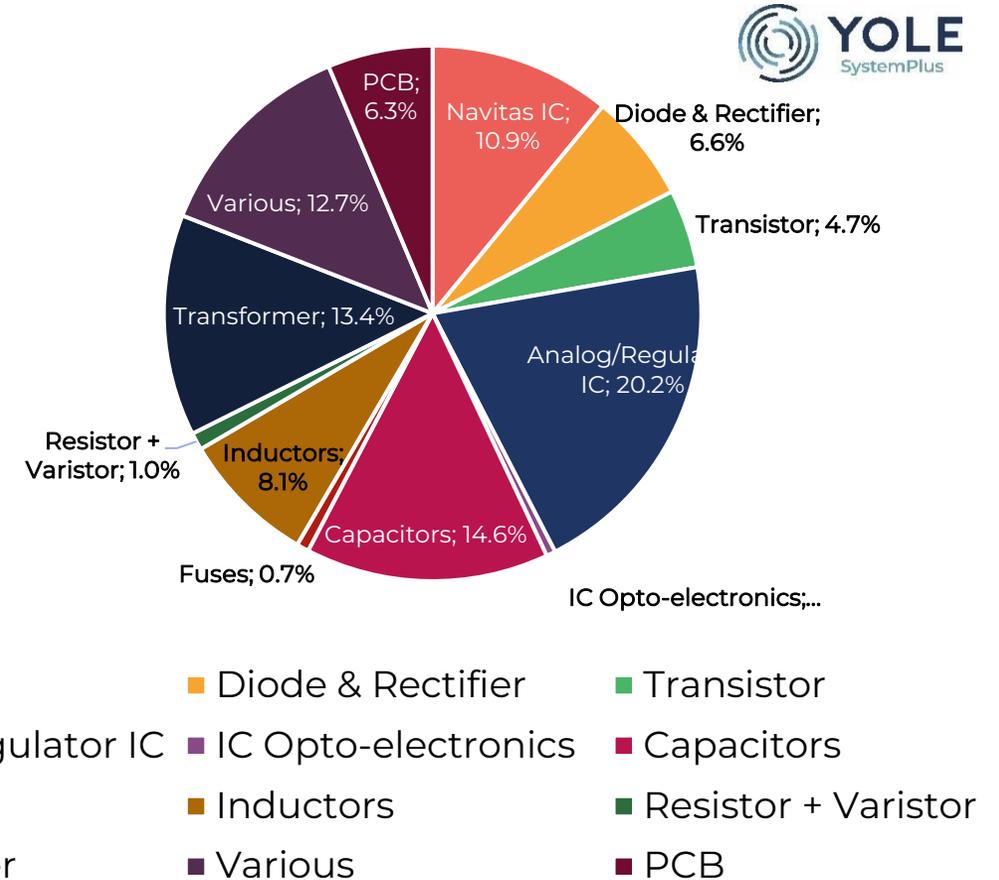
Use of GaN to replace Si requires a different design considerations.

COST COMPARISON GAN VS SI CHARGER – SYSTEM LEVEL

Samsung 45W charger EP-T4510 (using Navitas NV6014 GaNFast IC)

Component Category		Items	% of total Chip Set Cost
Power	Navitas IC	1	10.9%
Power	Diode & Rectifier	12	6.6%
Power	Transistor	5	4.7%
IC	Analog/Regulator IC	2	20.2%
IC	IC Opto-electronics	1	0.6%
Passive	Capacitors	29	14.6%
Passive	Fuses	1	0.7%
Passive	Inductors	6	8.1%
Passive	Resistor + Varistor	44	1.0%
Passive	Transformer	1	13.4%
Mechanics	Various	1	12.7%
Mechanics	PCB	1	6.3%
Total		104	100.0%

Samsung EP-T4510 (Navitas IC)
 BOM Cost Breakdown



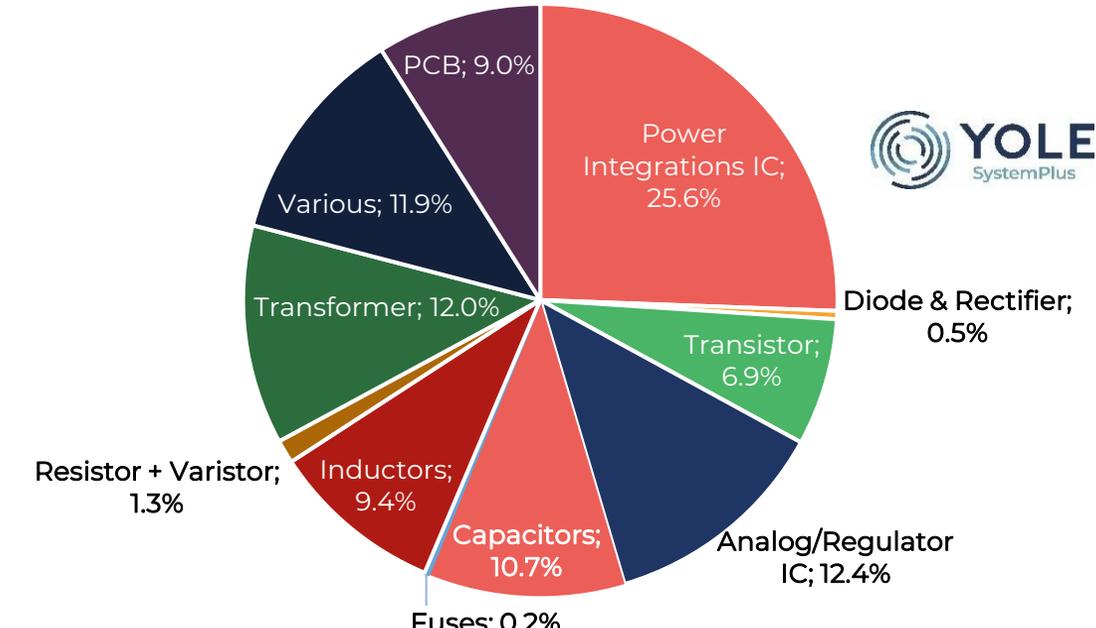
- The regulator IC components represents 20% of the BOM Cost.
- Navitas GaN IC cost contribution is just 10.9% of the total BOM Cost

BOM COST COMPARISON

Samsung 45W charger EP-TA845 (Power Integrations SC1710 IC)

Component Category		Items	% of total Chip Set Cost
Power	Power Integrations IC	1	25.6%
Power	Diode & Rectifier	5	0.5%
Power	Transistor	4	6.9%
IC	Analog/Regulator IC	2	12.4%
IC	IC Opto-electronics	0	0.0%
Passive	Capacitors	28	10.7%
Passive	Fuses	1	0.2%
Passive	Inductors	2	9.4%
Passive	Resistor + Varistor	30	1.3%
Passive	Transformer	1	12.0%
Mechanics	Various	1	11.9%
Mechanics	PCB	1	9.0%
Total		76	100.0%

Samsung EP-TA845 (Power Integrations IC) BOM Cost Breakdown



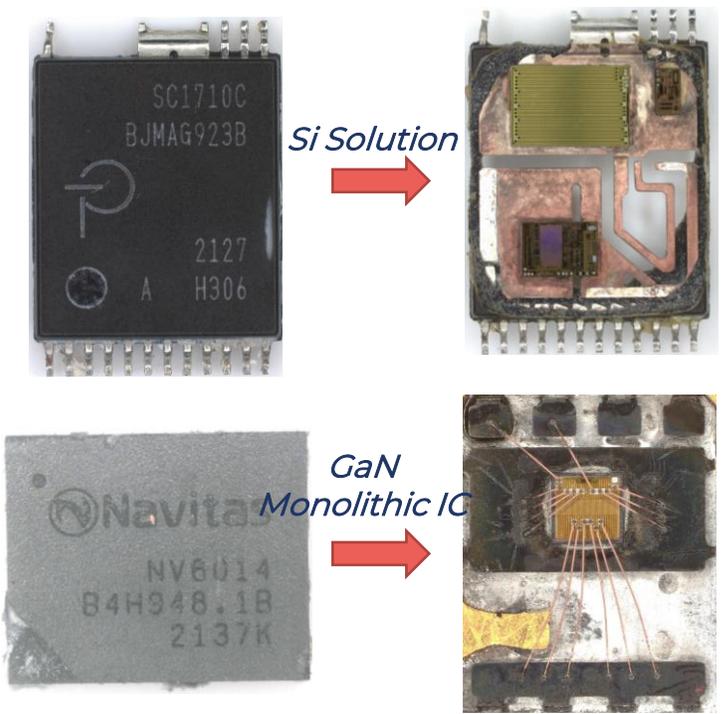
- **Power Integrations SC1710 IC represents 25.6% of the BOM Cost.**

- Power Integrations IC
- Transistor
- Capacitors
- Inductors
- Transformer
- PCB
- Diode & Rectifier
- Analog/Regulator IC
- Fuses
- Resistor + Varistor
- Various

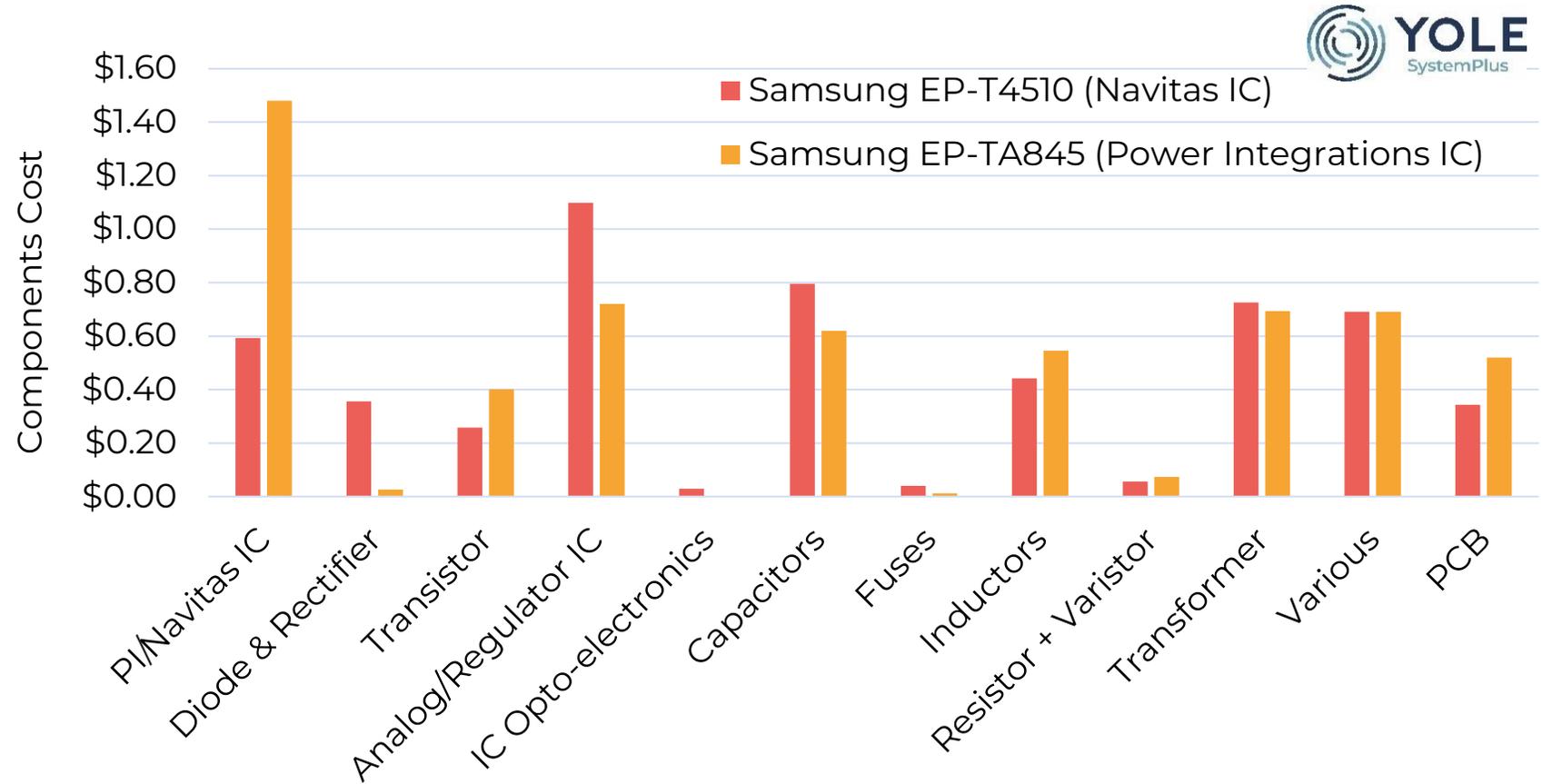
BOM COST COMPARISON

Samsung 45W charger EP-T4510 vs EP-TA845 model

- Although Samsung EP-TA845 model uses less components, its total BOM cost is still higher than that of the EP-T4510 model.
- The Power Integrations IC Si based IC in EP-TA845 model cost more than the Navitas GaN IC used in the EP-T4510 model.



BOM Cost Comparison of Samsung EP-T4510 & EP-TA845



Is GaN winning the cost challenge?

RECOMMENDATIONS AND CONCLUSION

For further cost savings on GaN adoptions in power devices, the following propositions are made:

- Yield improvements on wafer level.
- Transition to larger wafer size (200 mm)
- Design awareness for cost savings.
- Review of current business model towards vertical integration.
- More market adoption (in automotive, data centers) could reduce price of device in the markets.

Thank you for your attention